Resin Deformation Analysis in UV Imprint Considering UV Shrinkage, Thermal Deformation, and Thermochemical Kinetics

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Background

- UV imprint is known as a low-cost and high-throughput nano/micro fabrication method.
- In recent years, it has been adopted as a fabrication method for micro-optical devices such as micromirror array that requires high-precision surface profiles.



Optical device produced by thermal imprint. Parity Innovations Co., Ltd.

https://www.piq.co.jp/about_e.html







Issue

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UV resin undergoes several percent thermal deformation and UV shrinkage during imprint, resulting in unexpected surface curvature when a soft mold is used.



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Related research

A numerical modeling method for thermal imprint has already been proposed.

- Thermo-viscoelastic constitutive model for thermoplastic resin:
 - Thermal deformation: heat expansion coeff.
 - Shear behavior: viscoelastic (generalized Maxwell model)
 - Temperature dependency:
 time-temperature superposition (WLF law)
- Finite element method



Example of thermal imprint analysis

Idea: It may be possible to achieve UV imprint modeling with a similar approach.







Our approach

Focusing on the analogy with thermo-viscoelastic model in thermal imprinting:
 UV reaction progress ⇒ Cooling
 UV curing ⇒ Cooling solidification
 UV shrinkage ⇒ Cooling contraction i.e., giving a virtual cooling of UV resin.
 To give virtual cooling, we introduce the idea of

"virtual temperature".







Idea of "virtual temperature"

Virtual temperature (θ^{virt}) is introduced as a measure of UV reaction progress to cool the UV resin virtually.

<u>e.g., UV curing \Rightarrow Cooling solidification</u>



Objective

- Establishment of numerical modeling method for resin deformation analysis in UV imprints considering
 - 1. UV curing,
 - 2. UV shrinkage,
 - 3. thermal deformation, and
 - 4. temperature-dependent reaction rate.
- Validation of the modeling method with a micromirror array example for aerial display.

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Experiments







Resin temperature measurement test

<u>Outline</u>

- UV resin is dropped on a PDMS block placed on a glass substrate.
- UV light is exposed from below.
- A thermal imaging camera measures resin temp. from above.
- The test specifications are identical to those of the actual micromirror array imprint.
 - Cation polymerization-type resin
 - Hard PDMS with Young's modulus of 5 MPa
 - UV-LED flat light of 365 nm
 - 30 s exposure with 50 mW/cm²









Resin temperature measurement test

<u>An example result (300 mW/cm² case)</u>



The temp. reaches the maximum in several seconds

after the start of exposure and gradually returns to room temp..

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Resin temperature measurement test

Time histories of temp. and expansion (50 mW/cm², 30s)



A temperature increase about 100 K causes about 1% thermal linear expansion (3% expansion in volume)

in 6 s after exposure.

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UV shrinkage & complex shear modulus meas. tests *Outline*

- Rotational oscillatory rheometer.
- Small rotational oscillation is given to the UV resin under UV curing.
- Time history of UV shrinkage (gap length) is measured.
- Time history of Complex shear modulus at various temps. and freqs. is also measured.
- Resin temp. is kept constant by the aluminum rod with temp. control.

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Same UV exposure condition as the micromirror array imprint.

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UV shrinkage & complex shear modulus meas. tests

Time history of UV shrinkage (at 40 °C, independent of freq.)



UV curing finally causes about

0.7% linear shrinkage (2% shrinkage in volume)

 \Rightarrow It seems possible to treat this as virtual "thermal" contraction

by combining this with the real thermal expansion.

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UV shrinkage & complex shear modulus meas. tests<u>Time history of complex shear modulus at various temps.</u>(1 Hz in freq.)Left: Storage shear modulus, Right: Loss shear modulus



UV curing progresses faster as the temp. increases. ⇒ It seems possible to identity the temp.-dependent reaction rate constants.







UV shrinkage & complex shear modulus meas. tests Time history of complex shear modulus at various freqs. (40 °C in temp.) Left: Storage shear modulus, Right: Loss shear modulus (a) 100 Hz 3 Hz 0.1 Hz 30 Hz 1 Hz 0.03 Hz 3.5×10^{8} $\begin{array}{c} 3.0 \times 10^8 \\ \text{Shear Modulus} \\ 3.0 \times 10^8 \\ \text{Solution} \\ \text{Sol$ (b) 5.0×10^{7} $\overset{\text{snppo}}{\underset{\scriptstyle \overset{\circ}{\mathcal{B}}}{\overset{\circ}{\mathcal{B}}}} 3.0 \times 10^7$ 40.0°C, Control 100 - Control ⁴Closs 1.0×10⁷ Storage at 40 1.0×10^{8} 0.0×10^{0} 5.0×10^7 600 1200 2400 3000 3600 1800 Time, t(s) 0.0×10^{0} 600 1200 1800 2400 3000 3600 0 Time, t(s)

The storage modulus becomes larger as the freq. increases. \Rightarrow It seems possible to identify the Prony series of the generalized Maxwell model and the time-(virtual)temperature superposition law.

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Methods







Identification of Arrhenius Constants

Sampling Points Arrhenius Equation Approx

60

Temperature, θ^{real} (°C)

80

100

- The reaction rate scaling factor $k(\theta^{real})$ can be identified from the time history of the complex shear modulus at various temps. (right fig.).
- Based on thermochemical kinetics, the Arrhenius equation is used for curve fitting.

40

40

35

20 Scaling Factor, *k* 00 Scaling Factor, *k* 01 Scaling Factor, *k* 01 Scaling Factor, *k* 01 Scaling Factor, *k* 02 Scaling Factor, *k* 03 Scaling Factor, *k* 04 Scaling Factor, *k*

5

0

20



120

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Definition of virtual temp. time history

- $\theta^{\text{virt}} = 0$ before UV exposure ($t \le 0$).
- After UV exposure, θ^{virt} is monotonically decreased according to the reaction rate factor k at each moment.



Identification of virtual temp.-dependent expansion

- The previous plots of time-dependent thermal deformation and UV shrinkage are converted into virtual temp.-dependent plots.
- The sum of the two is the virtual temp.-dependent expansion



Identification of thermo-viscoelastic properties <u>Prony series coefs.</u>

The Prony series coefs. (g_i, τ_i) s are identified by the curve fitting for the master curves of storage/loss shear modulus.

 (g_i, τ_i) s are described as a table data.







Identification of thermo-viscoelastic properties

Time-virtul temp. superposition

The shift factor $A(\theta^{\text{virt}})$ for the time-virtual temp. superposition is identified by curve fitting using time shift data for the master



Now, a set of model parameters for UV resin deformation was all identified.

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Results and Discussion







Micromirror array imprint analysis

<u>Outline</u>

- Target pattern is a micromirror array for aerial display.
- Since the mold has repetitive structure, only one pattern is taken into account with periodic boundary conditions.
- The initial state is when the pattern is filled with UV resin.
- Commercial finite element code, ABAQUS, is used for simulation.
- 8-node hexahedral SRI element (C3D8) is adopted.

<u>Schematic view of</u> <u>micromirror array</u>



Optical device produced by thermal imprint. Parity Innovations Co., Ltd.

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Steps for imprint simulation

<u>Step 1: Initial state (0 s)</u>

 $\hfill\square$ Static analysis considering gravity

Apply non-separation & non-slip contact

<u>Step 2: UV exposure and dark curing (500 s)</u>

Quasi-static analysis (till the end)

 $\Box \text{ Decrease } \theta^{\text{virt}} (0 \rightarrow -312)$

<u>Step 3: Demolding and dark curing</u> (10 s)

- □ Remove the contact definition
- Lift up the mold

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- $\Box \text{ Decrease } \theta^{\text{virt}} (-312 \rightarrow -316)$
- Step 4: Dark curing (100000 s)

 $\Box \text{ Decrease } \theta^{\text{virt}} (-316 \rightarrow -41164)$

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Simulation result

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The periodic

conditions are

given correctly.

Major expansion

of UV resin soon

after UV exposure.

contraction of UV

resin during dark

Surface curve on

the PDMS mold

is reproduced.

boundary

Gradual

curing.

Comparison of results

Distribution of depth of curve on the top face



Actual Imprint (measured by laser microscope)

Simulation Result

The curvatures are in good agreement.







Comparison of results

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<u>Profiles of depth of curve on the vertical center line of the top face</u>



Summary







Summary

- A novel numerical modeling method for shape deformation analysis in UV imprint was proposed.
- UV curing, UV shrinkage, thermal deformation, and temperaturedependent reaction rate were all considered simultaneously by introducing the virtual temperature, reaction kinetics, and thermoviscoelastic constitutive law.
- A set of model parameters for UV resin was identified through the thermal camera tests and rheometer tests.
- A micromirror array imprint analysis was conducted to validate that the simulated surface curve agreed with the actual measurement with 10% error approximately.
- The temperature rise and thermal softening of the mold due to heat transfer are to be considered in the future.

Thank you for your kind attention!





